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SLW

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of: **IMAI, Genji**

Group Art Unit: **1752**

Serial No.: **09/976,279**

Examiner: **Yvette C. Thornton**

Filed: **October 15, 2001**

P.T.O. Confirmation No.: **1120**

For. **NEGATIVE PHOTOSENSITIVE RESIN COMPOSITION, NEGATIVE  
PHOTOSENSITIVE DRY FILM AND METHOD OF FORMING PATTERN**

**PETITION FOR EXTENSION OF TIME**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

September 22, 2004

Sir:

Applicants petition the Commissioner for Patents to extend the time for response to the Office Action dated March 25, 2004 for three months, from June 25, 2004, to September 25, 2004.

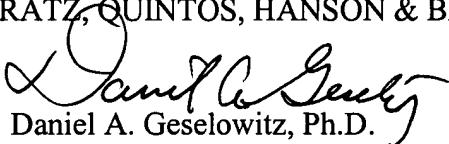
Attached please find a check in the amount of \$950.00 to cover the cost of the extension for a large entity. In the event that any additional fees are due in connection with this paper, please charge our Deposit Account No. 01-2340.

Respectfully submitted,

09/23/2004 FMETEK1 00000023 09976279 **ARMSTRONG, KRATZ, QUINTOS, HANSON & BROOKS, LLP**

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**Daniel A. Geselowitz, Ph.D.**

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Reg. No. 42,573

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PATENT TRADEMARK OFFICE